

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Ishiduka, et al. Examiner: Johnson, Connie P.

Application No.: 10/591,718 Group Art Unit: 1722

Confirmation No: 3280 Docket: 1608-7 PCT/US/RCE III

Filed: September 5, 2006 Dated: April 27, 2012

For: POSITIVE-TYPE RESIST COMPOSITION
FOR LIQUID IMMERSION LITHOGRAPHY
AND METHOD FOR FORMING RESIST
PATTERN

Commissioner for Patents
P.O. Box 1450
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Dated: April 27, 2012

Signature: Marcy Mancuso /*Marcy Mancuso*/

AMENDMENT AND RESPONSE ACCOMPANYING
A REQUEST FOR CONTINUED EXAMINATION

Sir:

This submission is in response to the final Office Action mailed on October 28, 2011, the due date for which is April 28, 2012, with a three-month extension of time. A Request for Continued Examination is being filed concurrently herewith. Entry of the amendments and reconsideration are respectfully requested.

Amendments to the Claims begin on page 2 of this submission.

Remarks begin on page 7 of this submission.